

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Tsuyoshi NAKAMURA, et al.

Application No.: To be assigned

Group Art Unit: To be assigned

Confirmation No.: To be assigned

Examiner: To be assigned

Filed: July 11, 2001

For: NOVEL COPOLYMER, PHOTORESIST COMPOSITION, AND PROCESS FOR
FORMING RESIST PATTERN WITH HIGH ASPECT RATIO

PRELIMINARY AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

Sir:

IN THE CLAIMS:

Please enter the following amended claims:

9. (Amended) A novel copolymer according to claim 1, wherein said novel copolymer has a weight average molecular weight (Mw) in terms of polystyrene of from 7000 to 30000 and a molecular-weight distribution (Mw/Mn, where Mn is a number average molecular weight) of equal to or less than 3.5.

REMARKS

The foregoing amendments are made in order to remove multiple dependencies and avoid the Government surcharge. Entry and consideration of this Amendment is respectfully requested.

Respectfully submitted,



Robert J. Seas, Jr.
Registration No. 21,092

SUGHRUE, MION, ZINN,
MACPEAK & SEAS, PLLC
2100 Pennsylvania Avenue, N.W.
Washington, D.C. 20037-3213
Telephone: (202) 293-7060
Facsimile: (202) 293-7860

Date: July 11, 2001

APPENDIX
VERSION WITH MARKINGS TO SHOW CHANGES MADE

IN THE CLAIMS:

The claims are amended as follows:

9. (Amended) A novel copolymer according to ~~any one of claims 1 to 8~~ claim 1,
wherein said novel copolymer has a weight average molecular weight (Mw) in terms of
polystyrene of from 7000 to 30000 and a molecular-weight distribution (Mw/Mn, where Mn is a
number average molecular weight) of equal to or less than 3.5.